

# History and potential of Non Evaporable Getter (NEG) technology

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*Technology Department  
Vacuum Surfaces and Coatings group*



EIROforum  
Science-Business WAMAS

Workshop on Advanced Materials and Surfaces  
CERN, November 2013

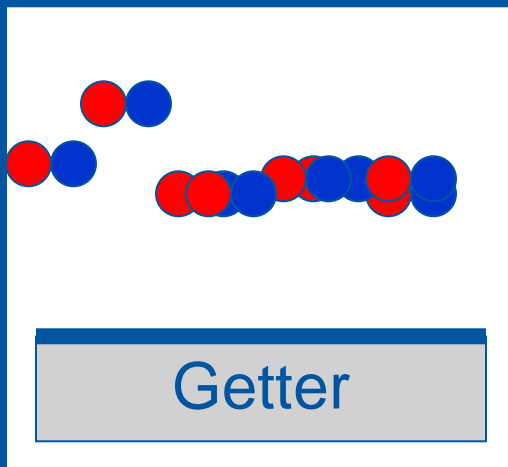
# OUTLOOK

- ① **Evaporable and Non Evaporable Getters**
- ② **Brief history of Getters**
- ③ **NEG technology at CERN**
- ④ **Potential of NEG coatings**
- ⑤ **Summary**

# 1 Evaporable and Non Evaporable Getters

Getters are materials capable of chemically adsorbing gas molecules (by chemisorption). To do so, their surface must be clean.

Chemisorption  
(surface pumping)



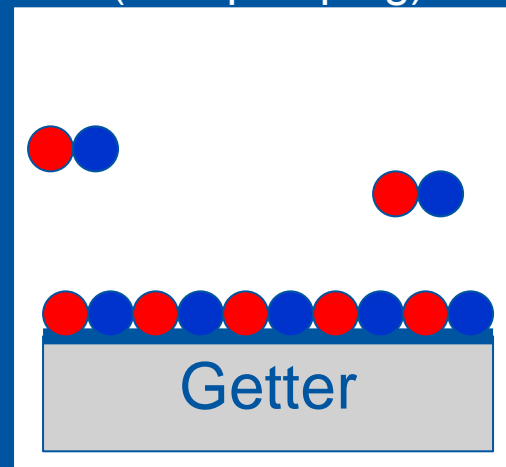
Limited to 1 monolayer ( $\sim 10^{15}$  molecules/cm<sup>2</sup>)

Reactive gases are pumped:

CO, O<sub>2</sub>, H<sub>2</sub>O, N<sub>2</sub>, H<sub>2</sub>, CO<sub>2</sub>

noble gases and methane are not pumped.

Diffusion  
(bulk pumping)



Very large capacity!

At **room temperature only H<sub>2</sub>** diffuses

Other reactive gases require higher temperature

# 1 Evaporable and Non Evaporable Getters

Getters are materials capable of chemically adsorbing gas molecules (by chemisorption). To do so, their surface must be clean.

Getters can be classified by the way the clean surface is obtained:

In situ deposition of a fresh getter film (under vacuum)



***Evaporable Getters***

Diffusion of the oxide layer into the bulk (usually by heating in vacuum)



***Non Evaporable Getters  
(NEG)***

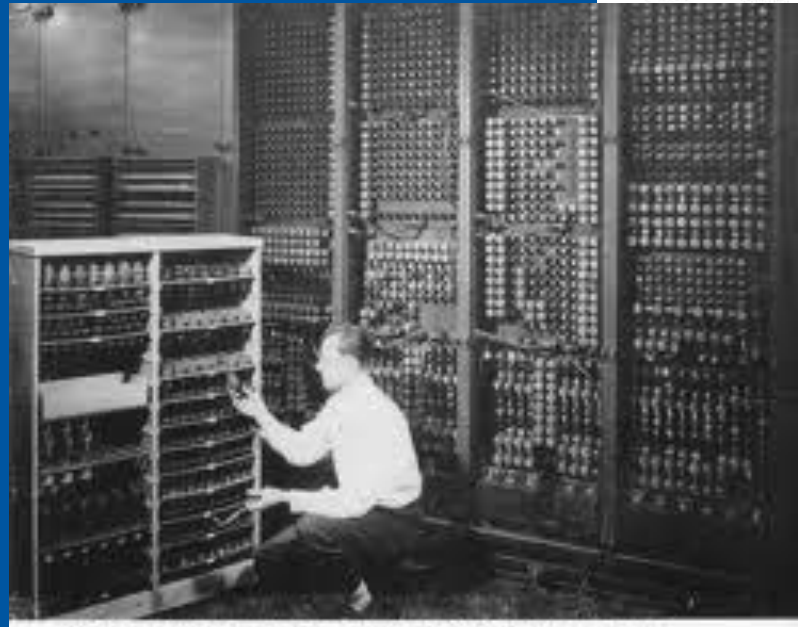
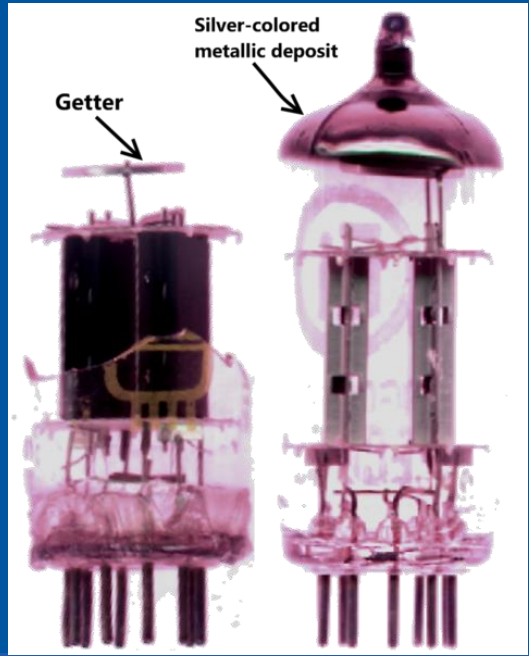
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# Evaporable Getters

Getter pumping was reported for the first time in 1858 by Plucker. When working with gas discharges in vacuum he noticed that *“certain gases react with the cathode and the platinum deposited in the walls”*.



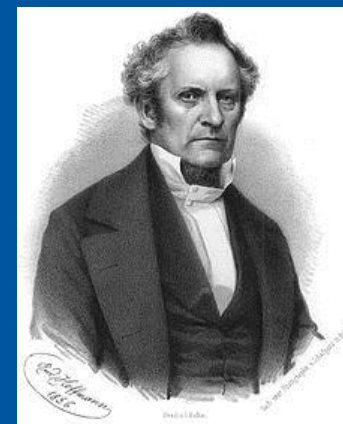
By the 1940s, industrialization of evaporable getters for vacuum tubes. (first phosphorous and then barium alloys). => reliability of electronics.



Replacing a bad tube meant checking among ENIAC's 19,000 possibilities.

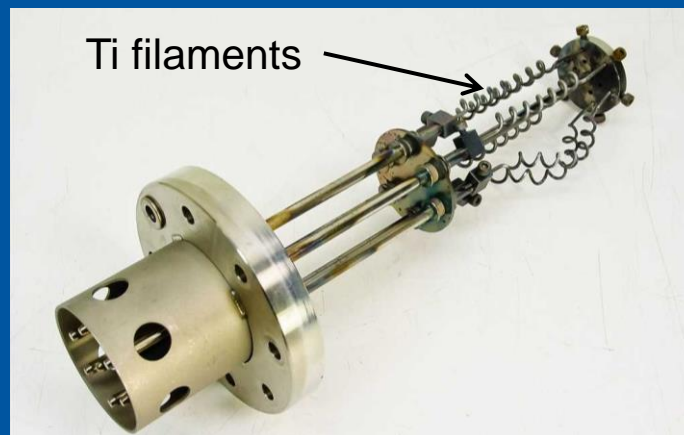


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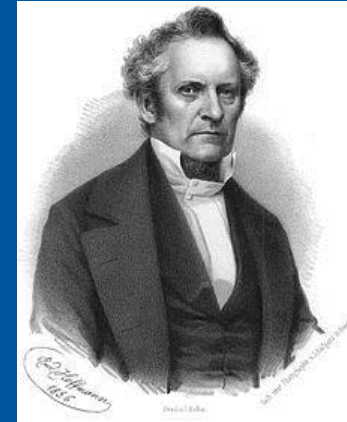


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In 1953 Herb invented the titanium sublimation pump (and in 1958 Hall invented the sputter ion pump, combining getter and ion pumping). => improve vacuum technology



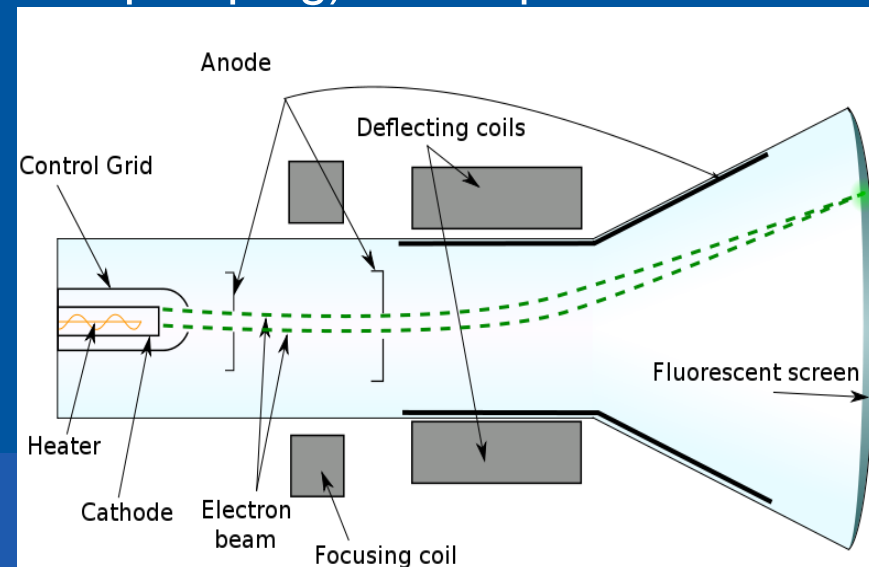
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1966 The Total Yield Flash Getter extended the life of color tv tubes from 300 to 10 000 hours. (SAES Getters)



1979 SAES Getters launches a Non Evaporable Getter (NEG) in form of strip. (developed with CERN for the Large Electron Positron collider).

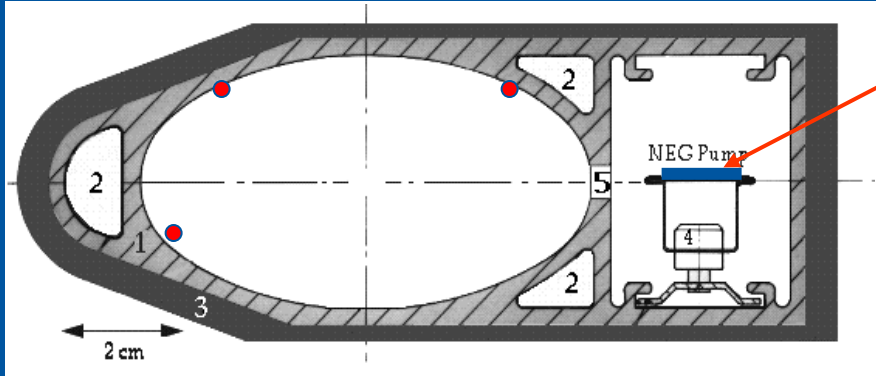




# 3 NEG technology at CERN

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Cross section of the LEP dipole vacuum chamber



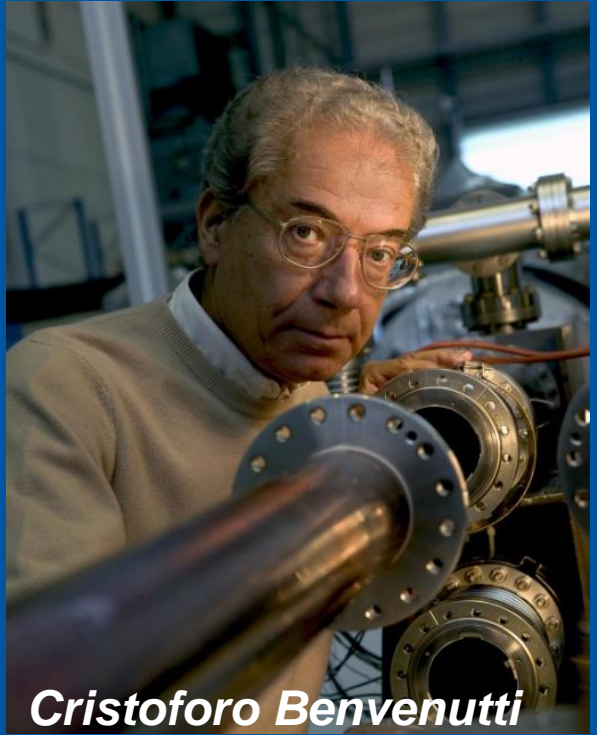
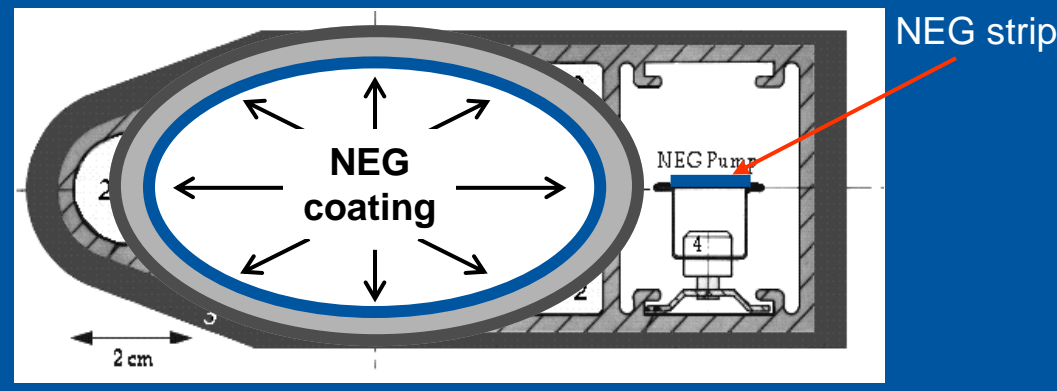
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1998 Low activation temperature NEG coatings,(Ti-Zr-V), developed at CERN for the LHC.

Cross section of the LHC dipole vacuum chamber



**Cristoforo Benvenuti**



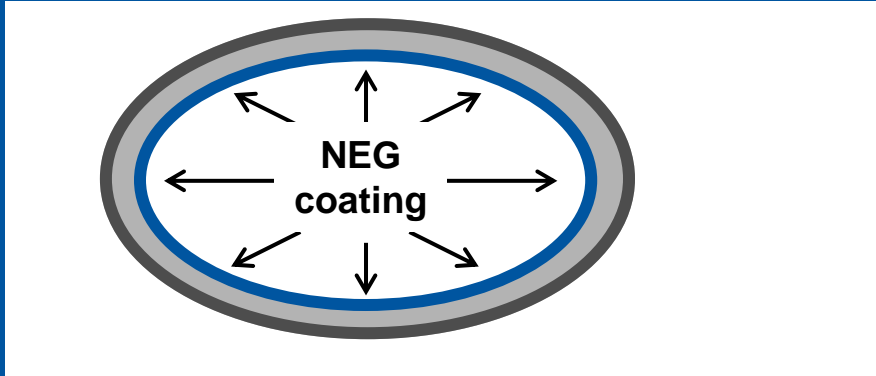
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Cross section of the LHC warm dipole vacuum chamber



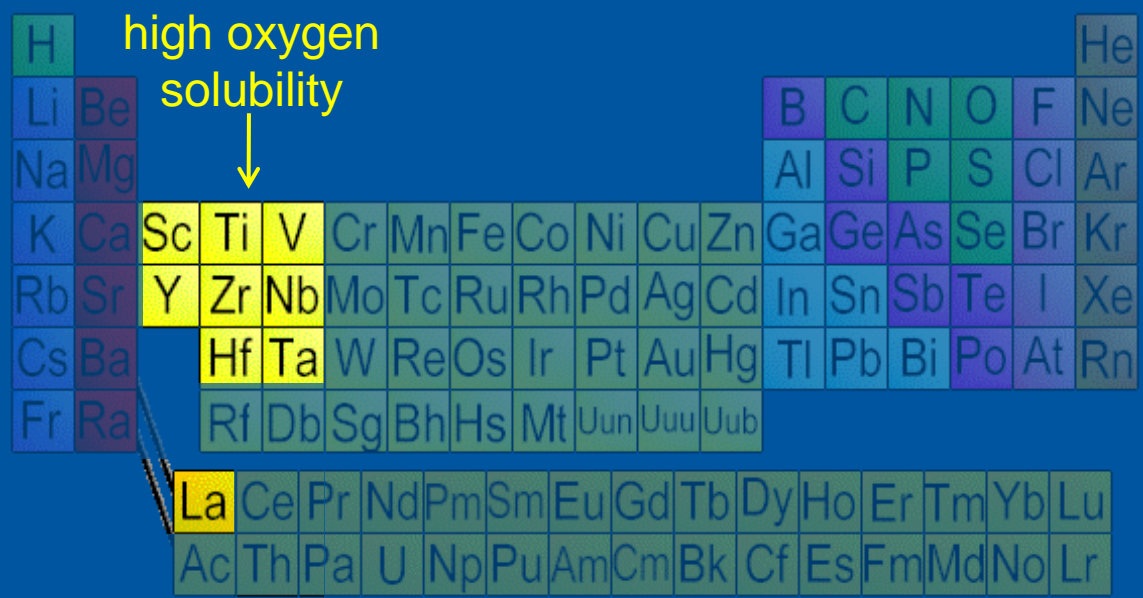
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# NEG technology at CERN

Known NEGs required very high activation temperatures (>> 350°C): Zr, Ti, Zr-Al, Ti-Al, Zr-V-Fe, Th-Ce-Al) (Usually as sintered powders or compressed in strips, pellets, rings)

CERN goal: find a **NEG with low activation temperature**. (compatible with the technical materials used for UHV: <400°C for stainless steel, <250°C for Cu, <200°C for Al)

More than 20 materials were investigated by combining 2 or 3 of this elements in the form of thin films. (Produced by DC Magnetron Sputtering)



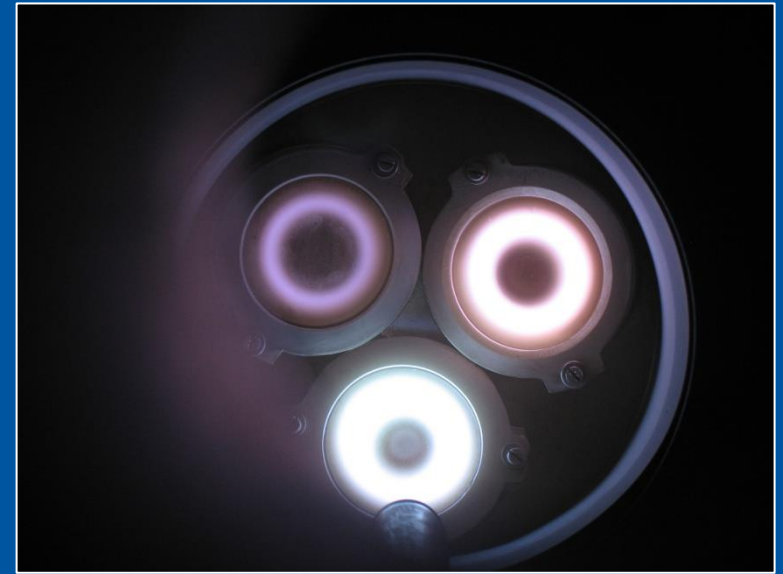
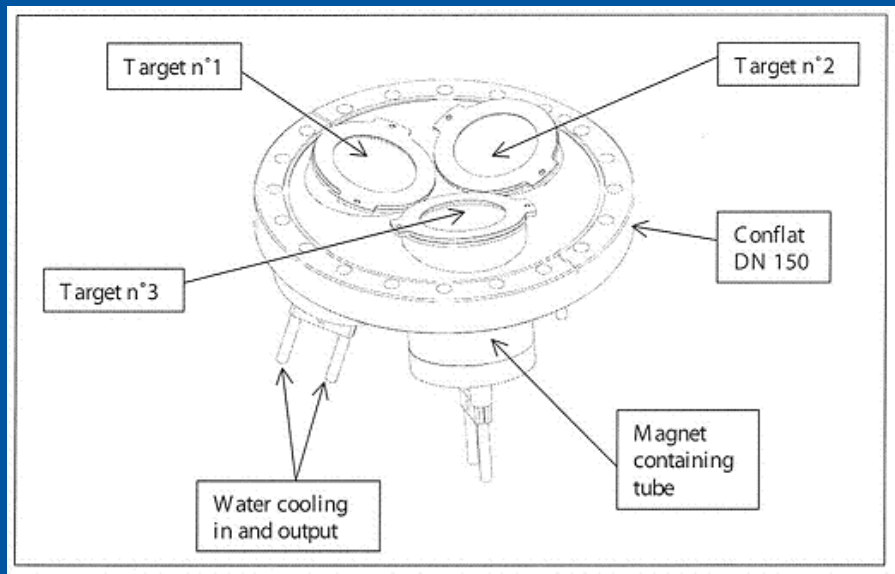
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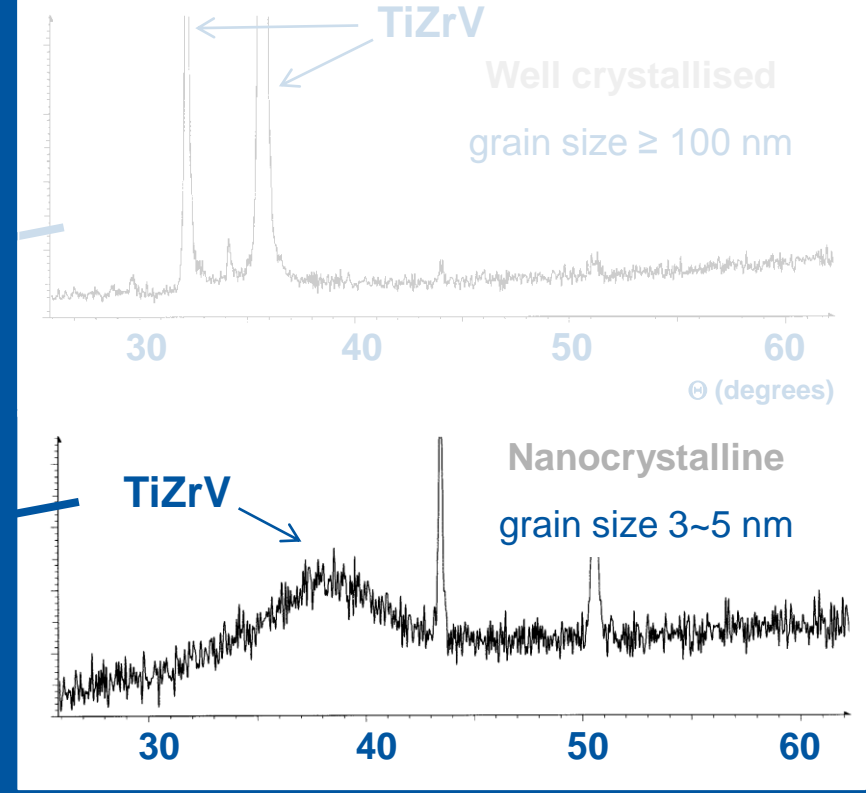
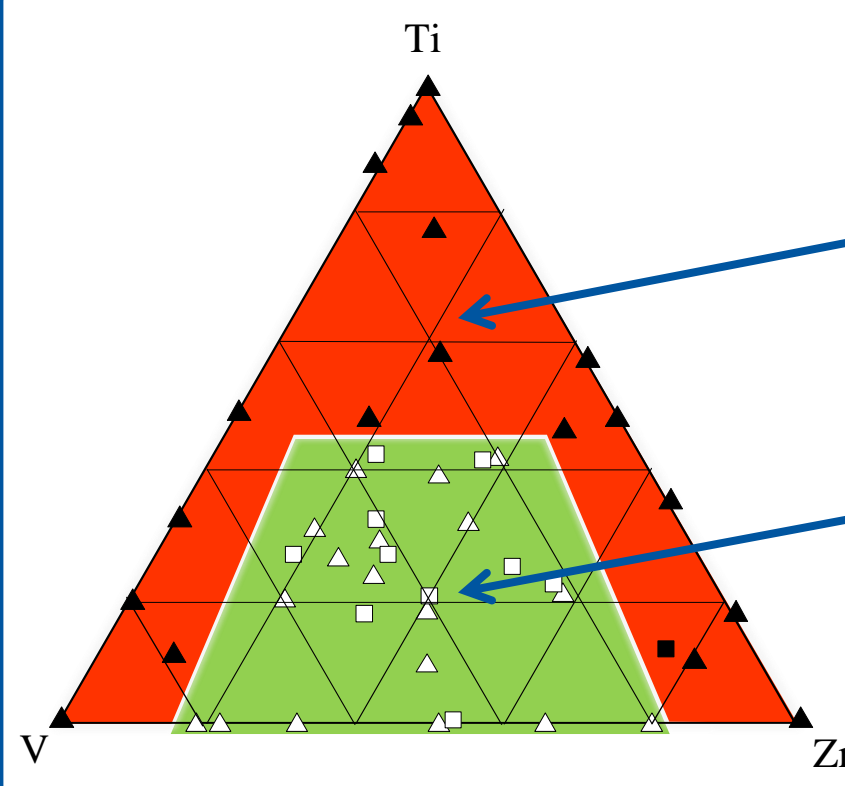


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## NEG technology at CERN

The **Ti-Zr-V** NEG coating can be activated at 180°C for 24 hours.

### Crystallographic structure (XRD)



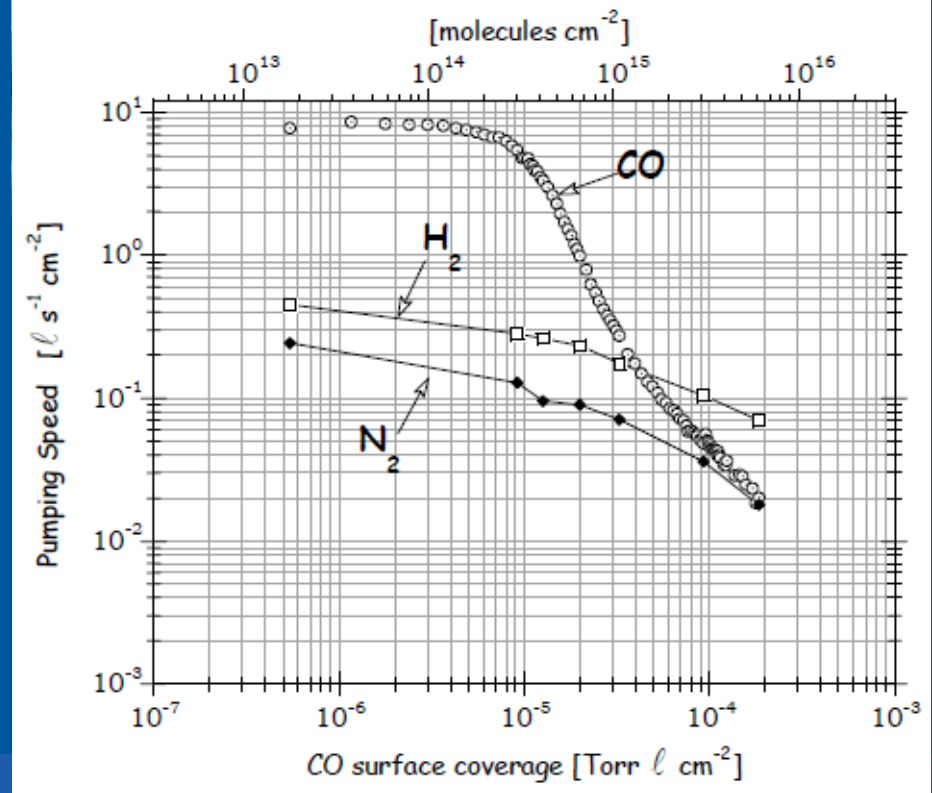
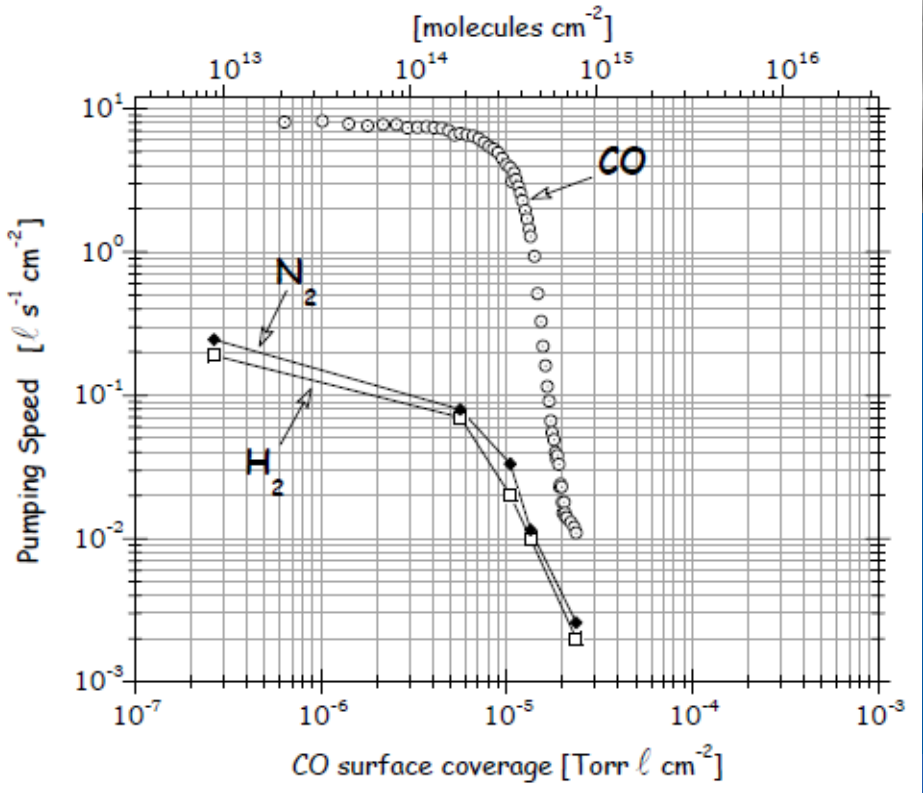
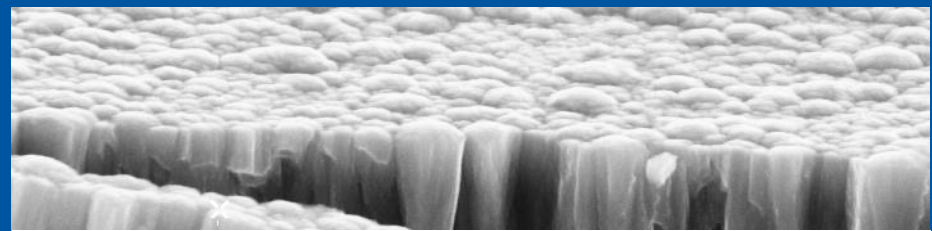
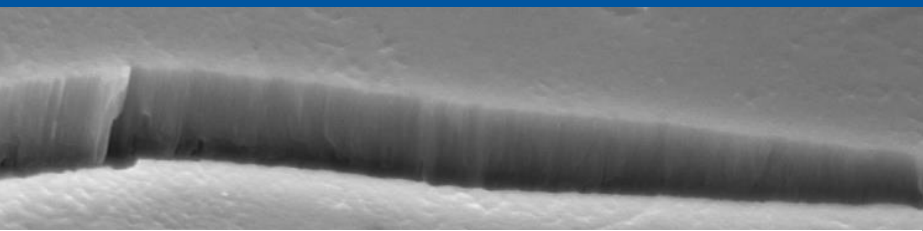
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# NEG technology at CERN

Vacuum properties 1: pumping speed versus coverage.

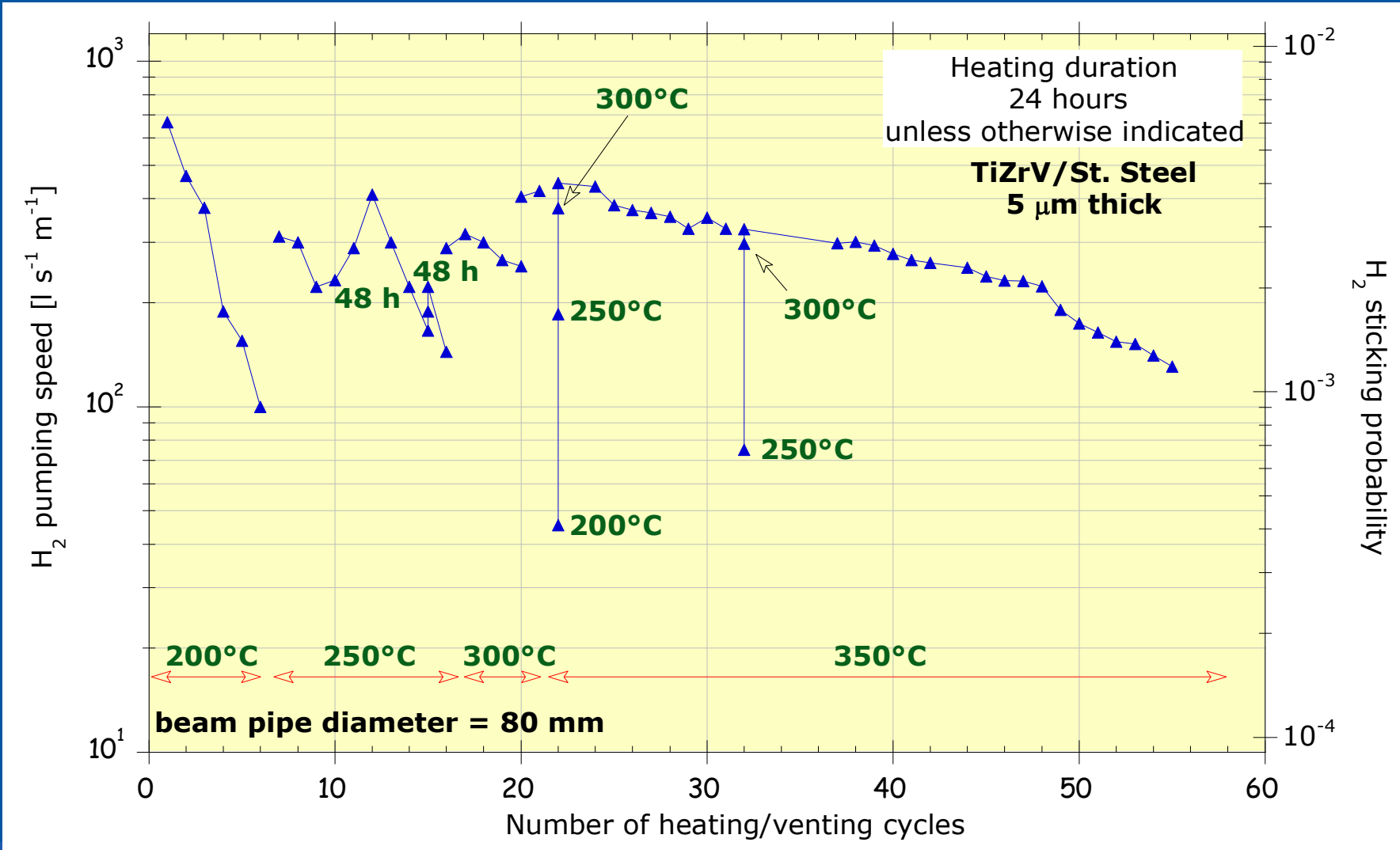
Smooth (coated at 100°C)

Rough (coated at 300°C)



# NEG technology at CERN

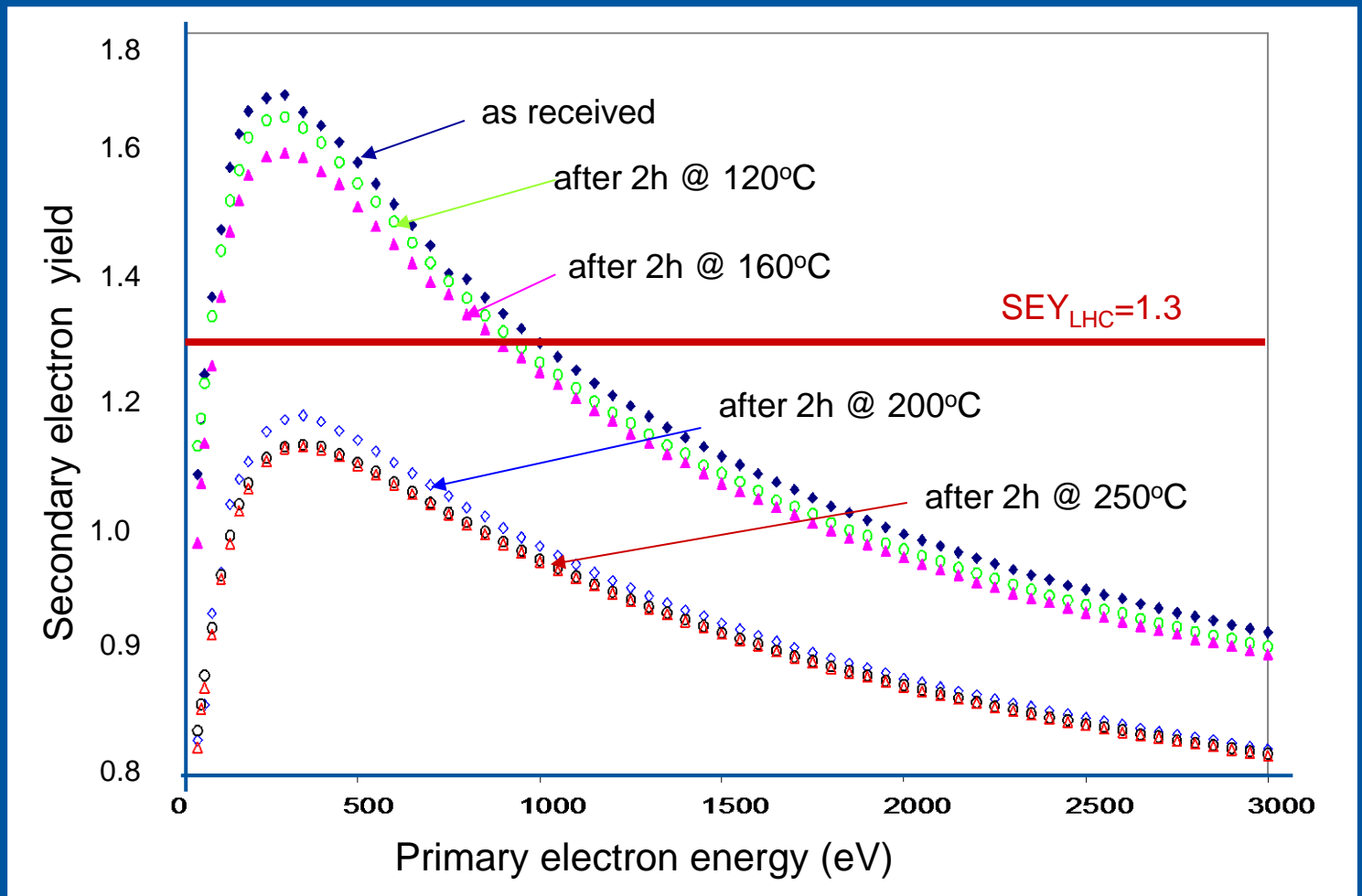
## Vacuum properties 2: ageing (recovery after air venting)





# NEG technology at CERN

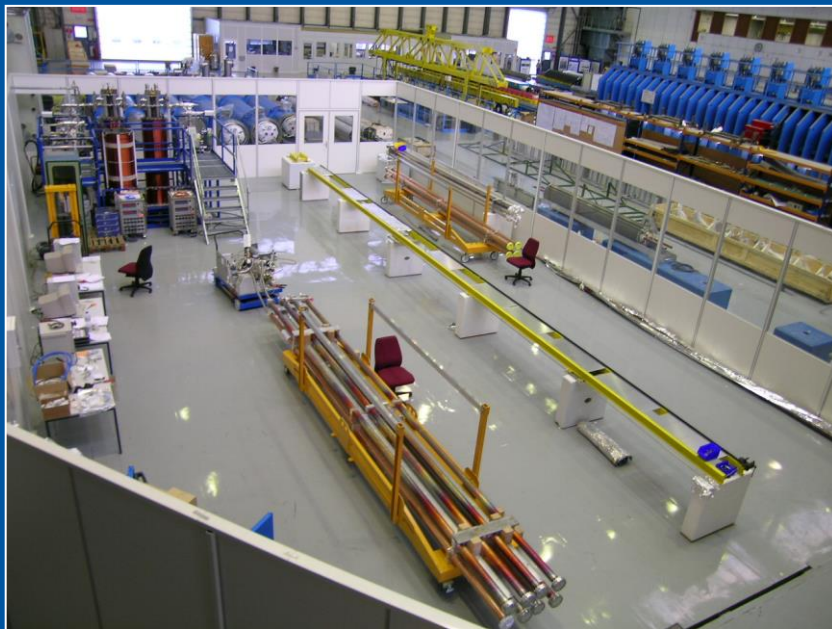
Anti electron multipacting properties 1: low Secondary Electron Yield (SEY).



**3**

# NEG technology at CERN

At CERN, large scale production for the LHC and experiments by DC Cylinder Magnetron sputtering (DCCM) from a target of Ti, Zr and V wires (more than 1300 chambers).

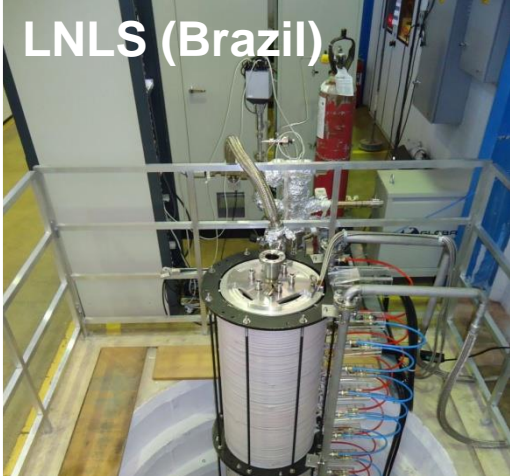


At CERN, large scale production for the LHC and experiments by DC Cylinder Magnetron sputtering (DCCM) from a target of Ti, Zr and V wires (more than 1300 chambers). AND WORLD WIDE: *producers under CERN license*

ESRF (France)



LNLS (Brazil)



SAES getters (Italy)



GSI (Germany)



FMB Berlin (Germany)

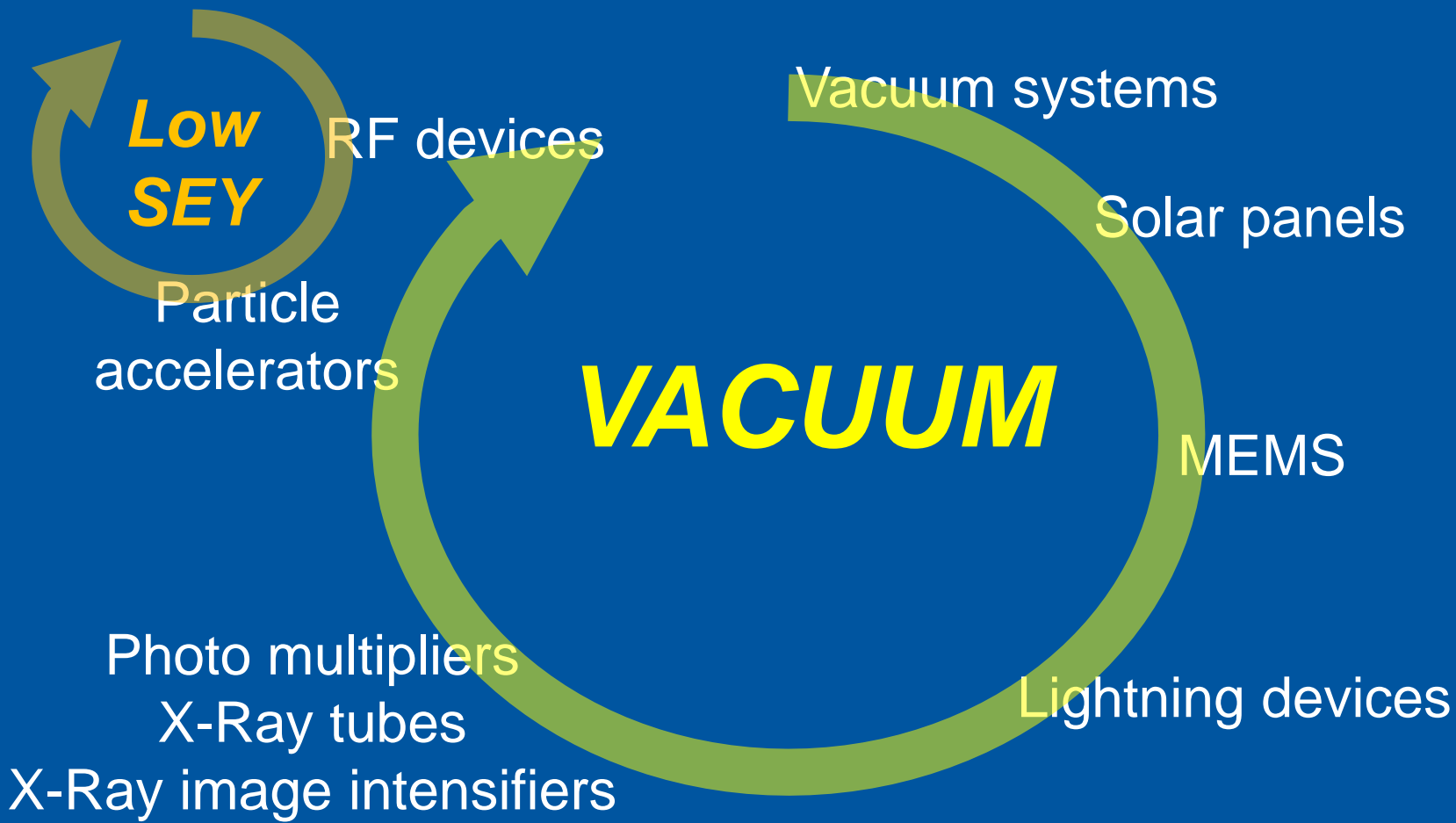


# Potential of NEG coatings

At CERN, large scale production for the LHC and experiments by DC Cylinder Magnetron sputtering (DCCM) from a target of Ti, Zr and V wires (more than 1300 chambers). AND WORLD WIDE: *users, in design/study*



Applications of NEG coatings other than in particle accelerators:



Due to their pumping properties, getters and NEG coatings became unavoidable in vacuum sealed devices.

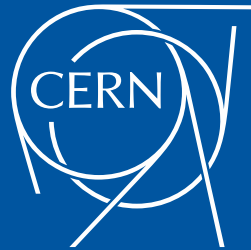
The development of particle accelerators pushed the development of NEG coatings with low activation temperature and in the form of thin film coatings.

The anti electron multipacting properties, (low SEY), of NEG coatings became of major importance for positive particle accelerators and can potentially be applied to waveguides and RF devices.

These coatings are applied in more and more accelerators but also in other technology devices (solar panels, MEMS, X-Ray imaging, etc)

Future developments targets lowering the activation temperature (150°C), deposition in small aperture devices (beam pipes) and integration in new assembly techniques.

Thank you for your attention.



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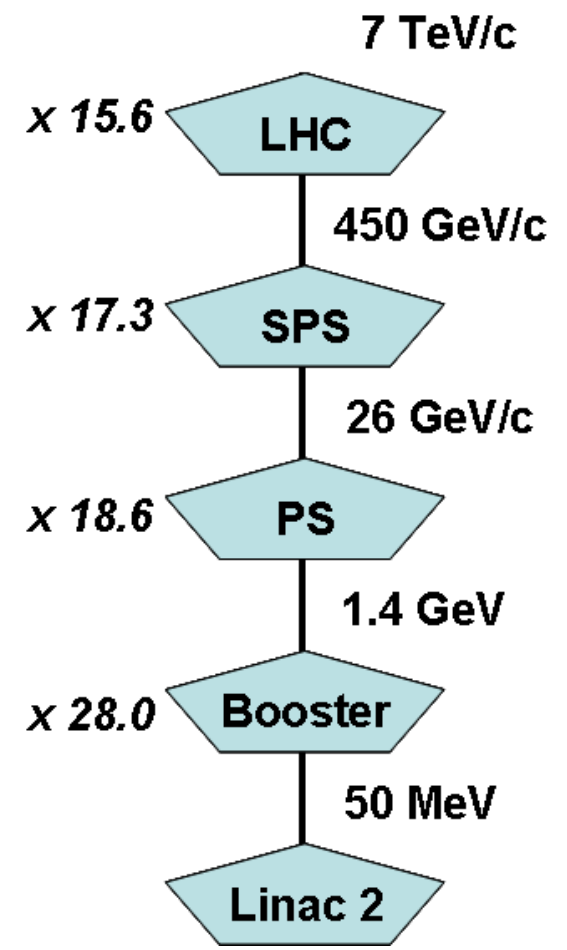
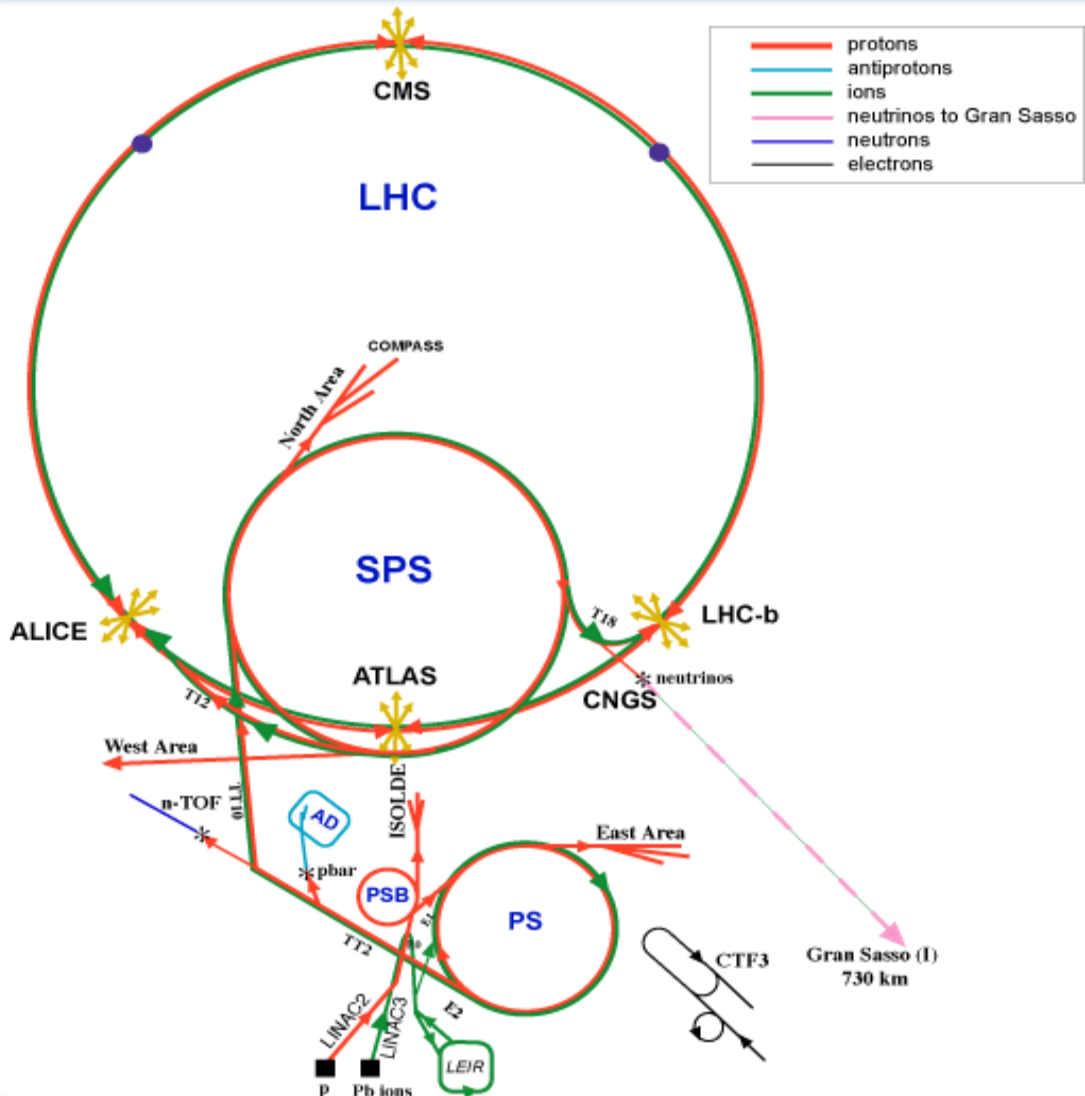
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# 1

# Introduction to CERN

CERN European Organization for Nuclear Research: *supplies particle accelerators and detectors to the scientific community to probe the fundamental structure of the universe*





## 2 Why do we need NEG and Carbon coatings

- Vacuum required to minimize interaction of particles with the residual gas.
- Long beam pipes => low conductance => requires ***distributed pumping.***
- To avoid electron multipacting, the internal walls of the beam pipes must have ***Low Secondary Electron Yield (SEY).***

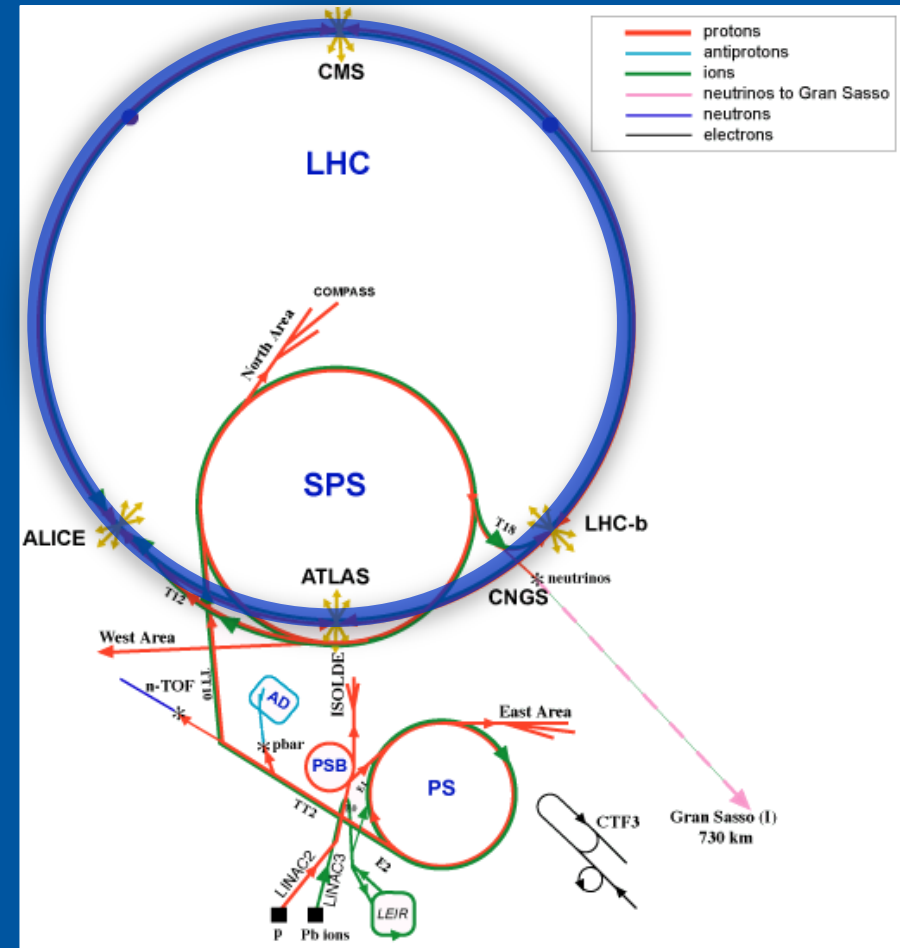
# 2 Why do we need NEG and Carbon coatings

## Motivation to develop NEG coating

### Long Straight Sections (LSS) of the Large Hadron Collider (LHC)

- Low pressure in long beam pipes
- Multipacting threshold  $SEY_{max}=1.3$
- Bakeable Beampipes ( $T>180^{\circ}C$ )

## CERN accelerators complex



# 2 Why do we need NEG and Carbon coatings

## Motivation to develop NEG coating

*Long Straight Sections (LSS) of the Large Hadron Collider (LHC)*

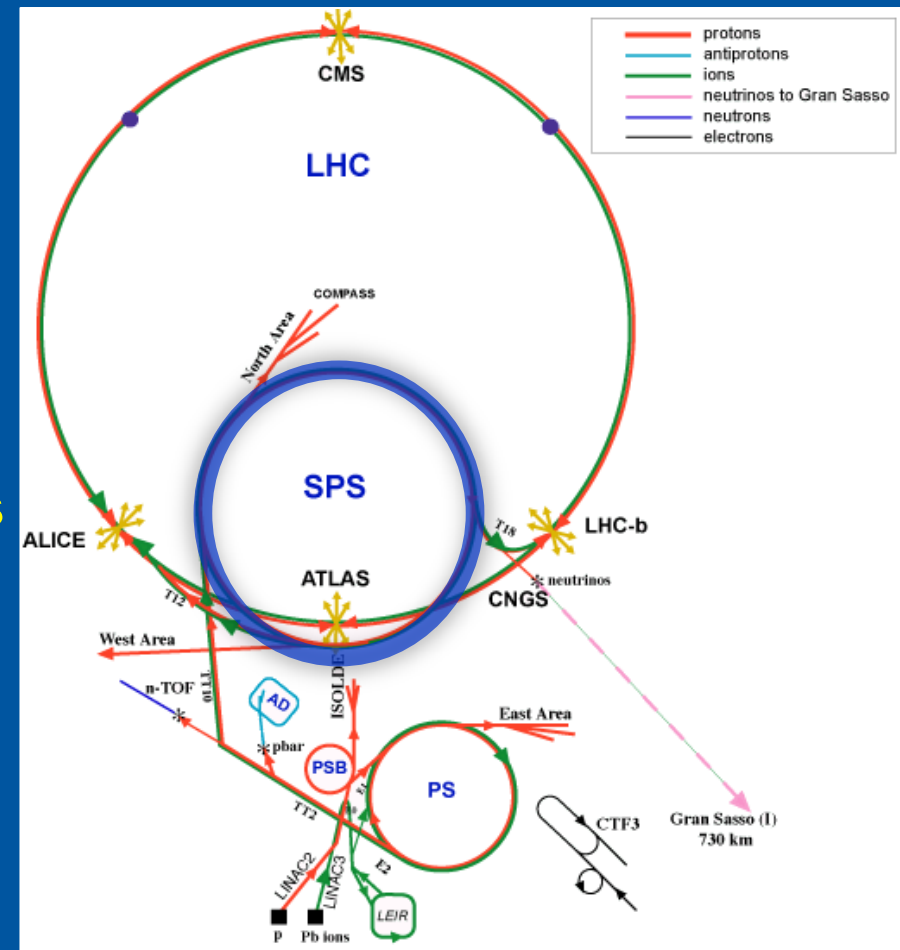
- Low pressure in long beam pipes
- Multipacting threshold  $SEY_{max}=1.3$
- Bakeable Beampipes ( $T < 350^{\circ}C$ )

## Motivation to develop Carbon coatings

*Upgrade the Super Proton Synchrotron (SPS)*

- Multipacting threshold  $SEY_{max}=1.3$
- **Non Bakeable Beampipes**

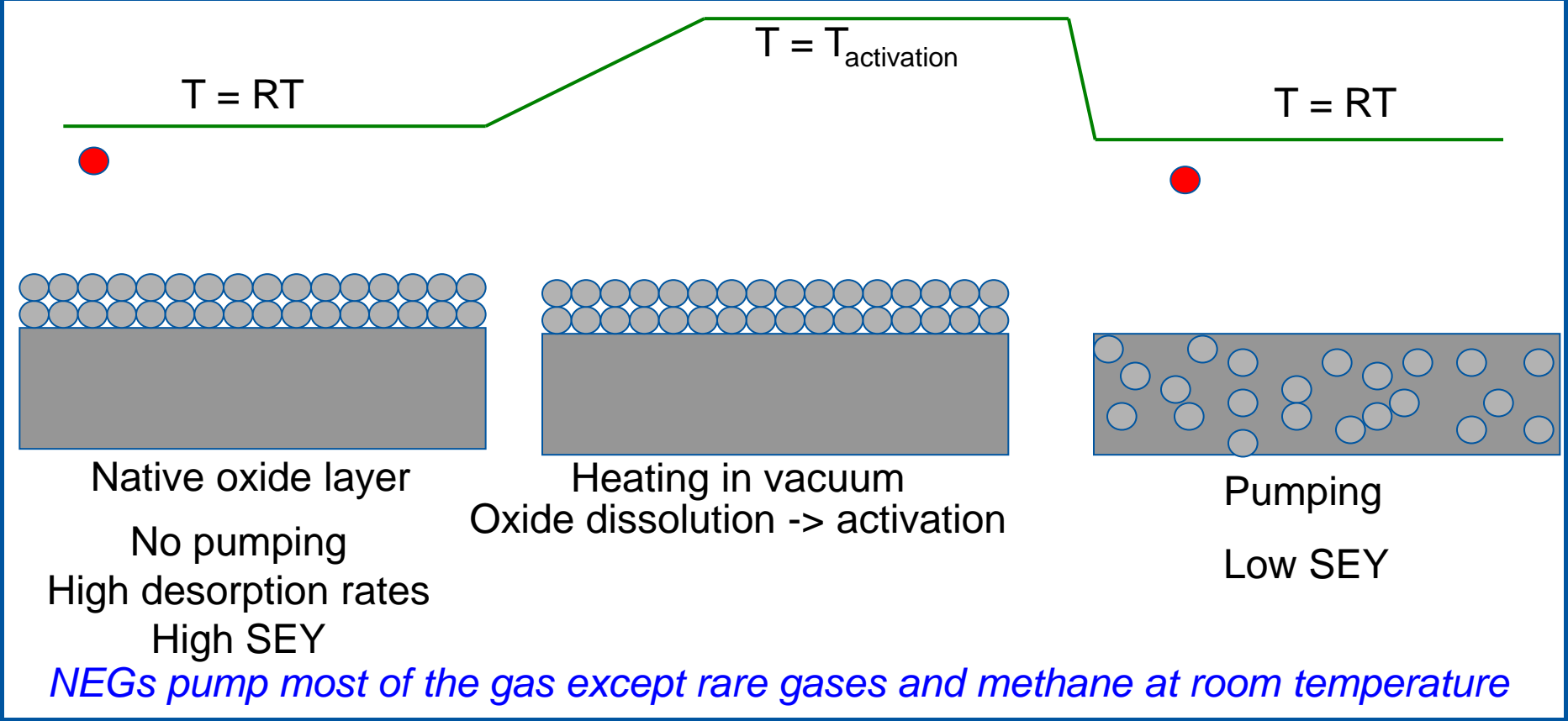
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# 3

# NEG coatings

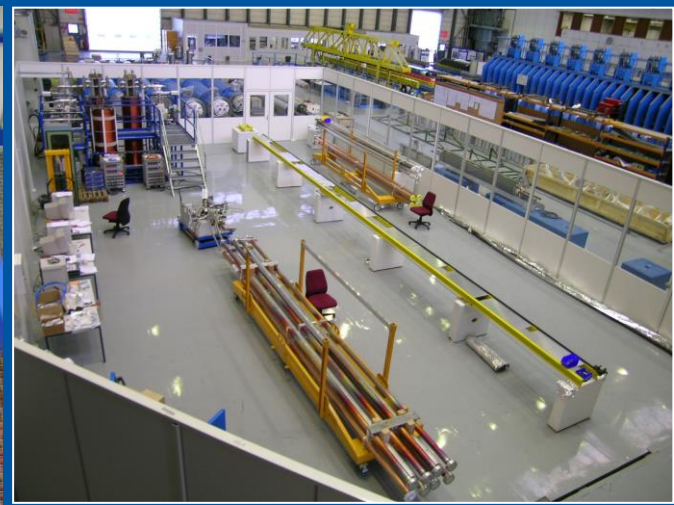
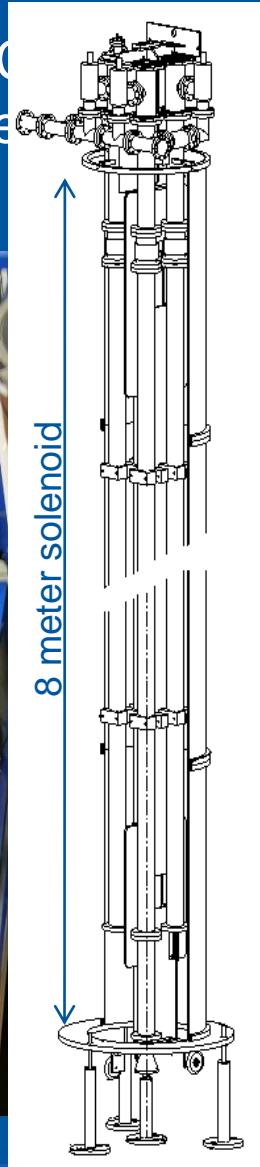
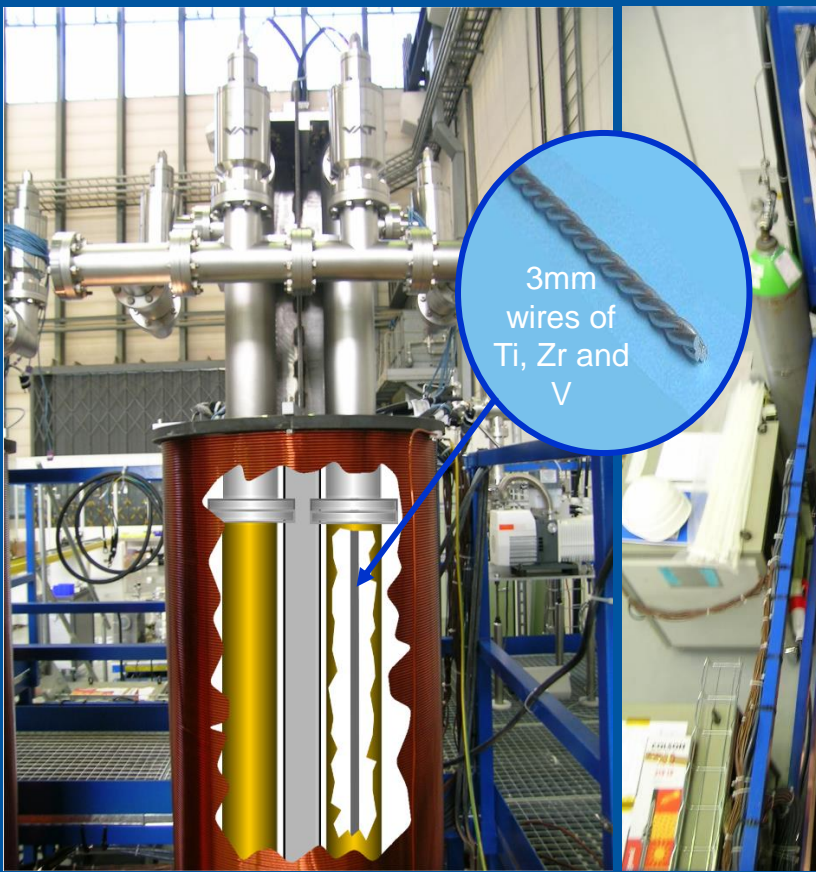
Getters are materials capable of chemically adsorbing gas molecules. To do so their surface must be clean. For Non-Evaporable Getters a clean surface is obtained by heating to a temperature high enough to dissolve the native oxide layer into the bulk.



# 3

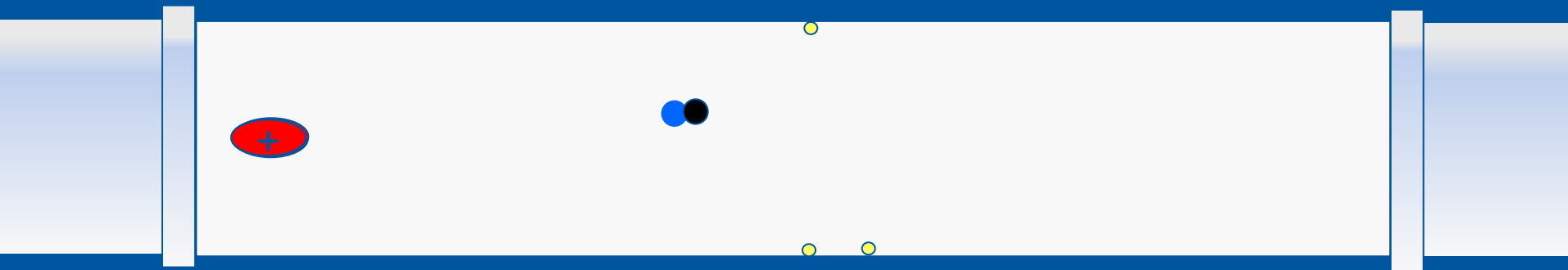
# NEG coatings

Large scale production for the LHC experiments by DC Cylinder Magnetron sputtering (DCCM) from a target and V wires (more than 1300 chambers)



## 2 Why do we need NEG and Carbon coatings

- Vacuum required to minimize interaction of particles with the residual gas.
- Long beam pipes => low conductance => requires ***distributed pumping*** instead of localized pumping
- To avoid electron multipacting, the internal walls of the beam pipes must have ***Low Secondary Electron Yield (SEY)***.



 Proton bunch (charge +)

 Gas molecule

 Electron (charge -)

## Multipacting properties 2: Electron Multipacting.

